

METHOD OF FILM DEPOSITION, AND FABRICATION OF STRUCTURES

ABSTRACT OF THE DISCLOSURE

11 A method of fabricating aluminum oxide films utilizing
aluminum alkoxide precursors is described. The aluminum
oxide film is formed by (a) providing an aluminum
alkoxide precursor that is dissolved, emulsified or
16 suspended in a liquid; (b) providing a vapor generated
from the aluminum alkoxide precursor; and (c) depositing
an aluminum oxide film on the substrate at a temperature
greater than 500°C.

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